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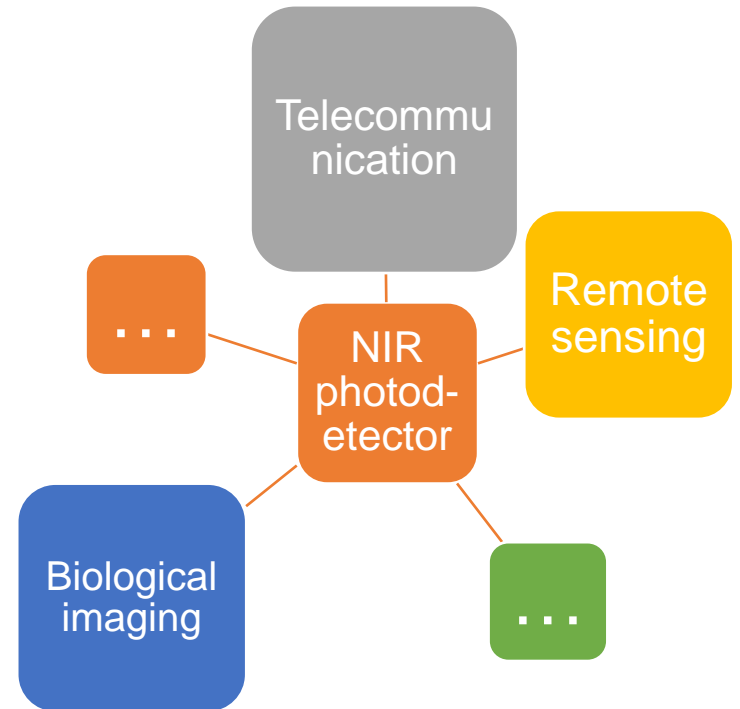
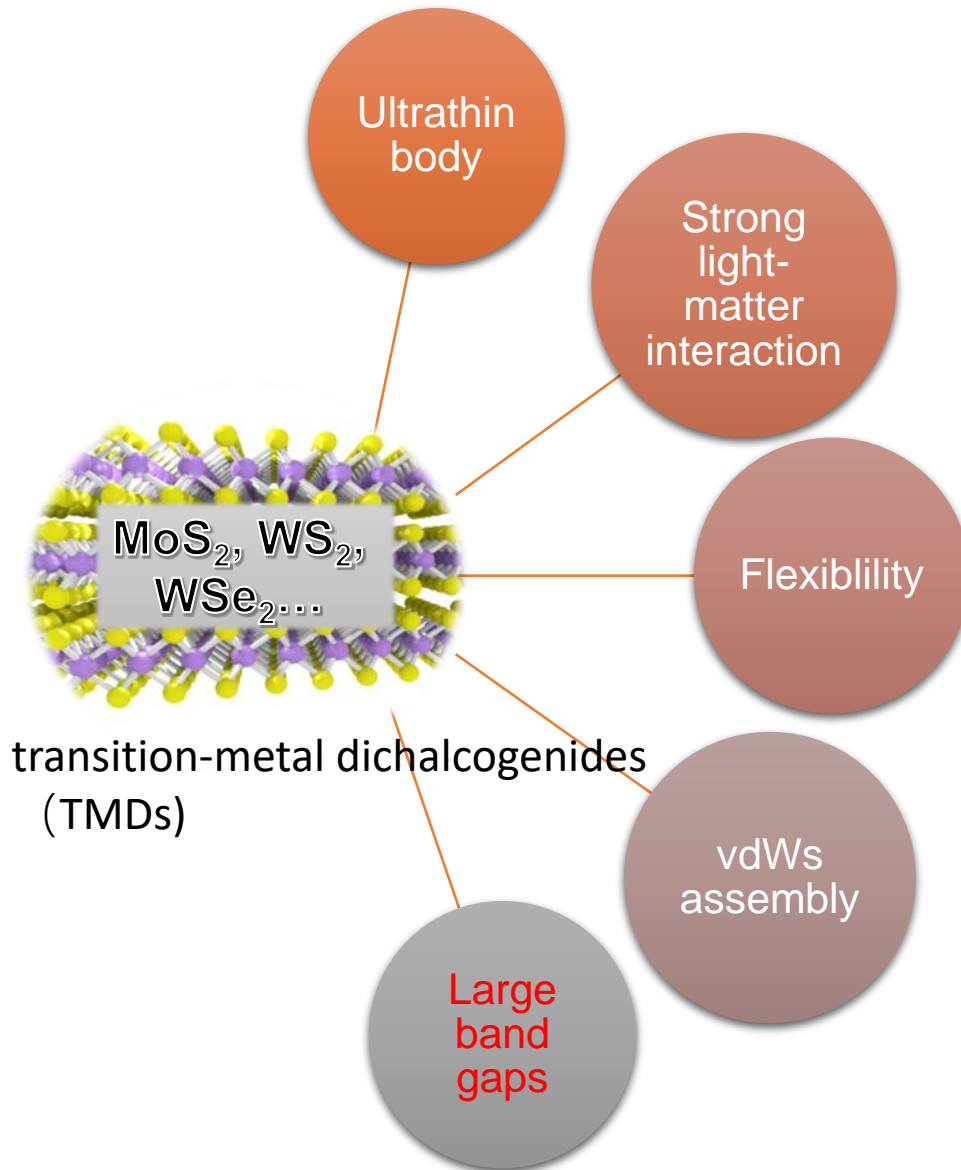
Ultrasensitive NIR Photodetectors Based on Graphene- MoTe₂-Graphene Vertical vdWs Heterostructure

Lun Dai

School of Physics, Peking University,

Beijing, China

Background and Motivation



Background and Motivation

We choose MoTe_2 , since its bandgap is about 1.0 eV in its bulk form .

Photoconductors Photodiodes

High responsivity

Low speed

External power supply

Low responsivity

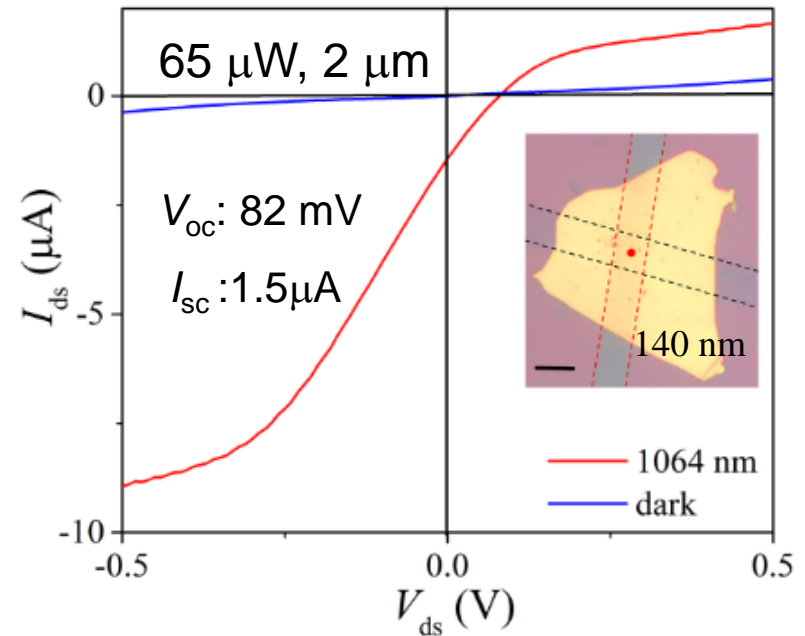
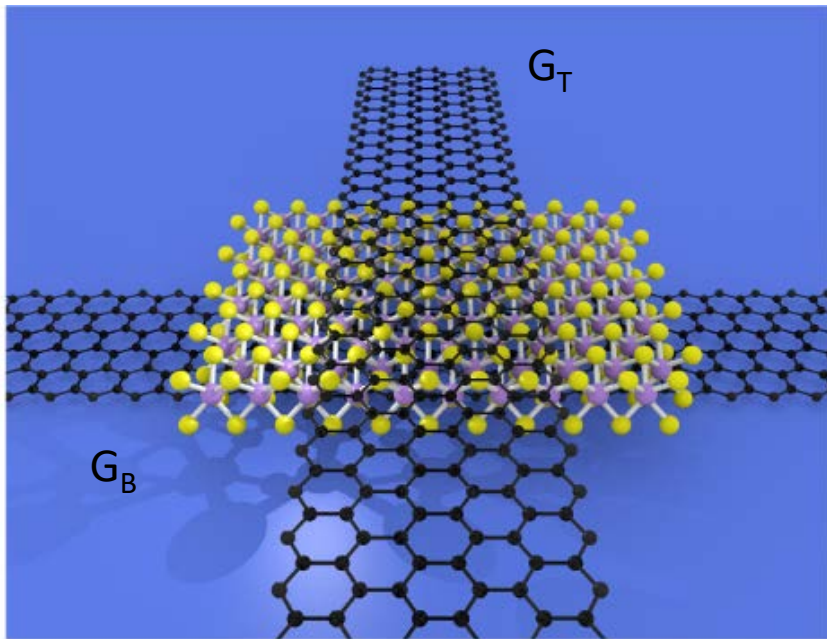
High speed

Without external power

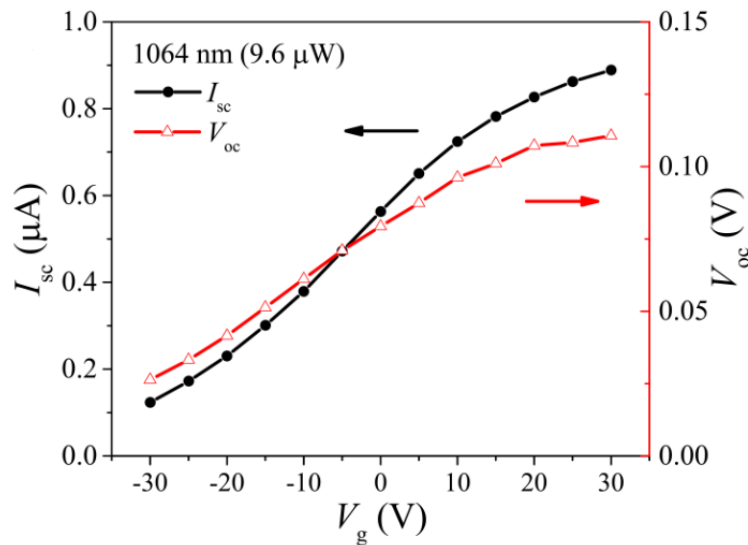
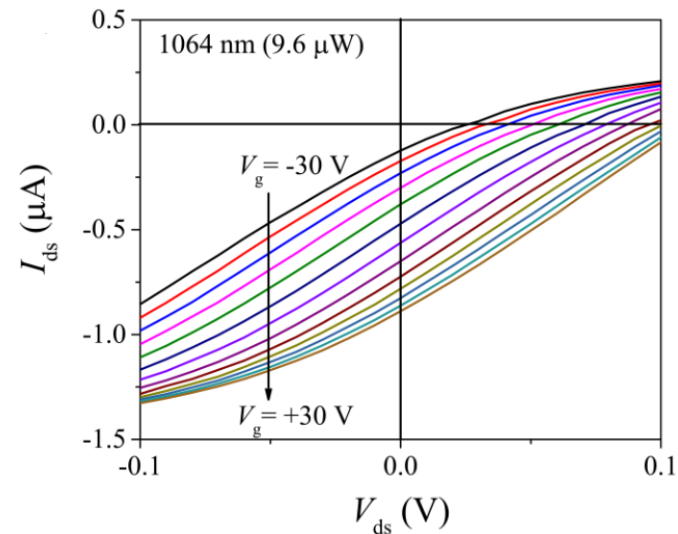
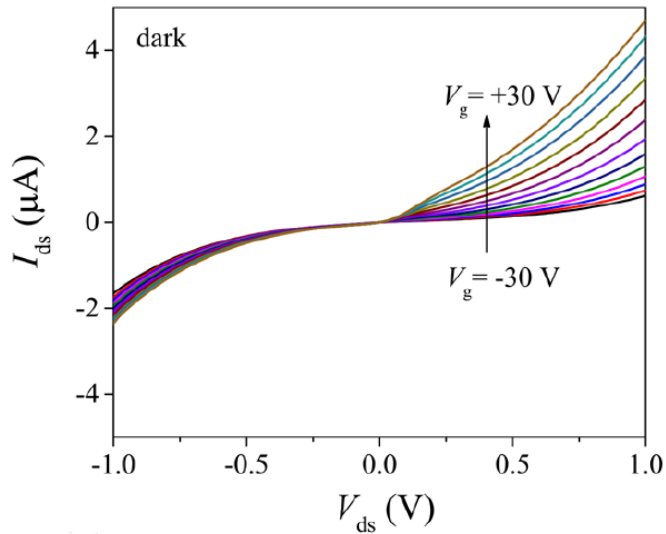
Graphene-MoTe₂-Graphene Heterostructure

Uniformly large photoresponse area and short transmit distance

- CVD graphene
- Exfoliated MoTe₂
- Microscale triangular knife
- PMMA layer
- 1064 nm NIR laser illumination
- Obvious photovoltaic behavior



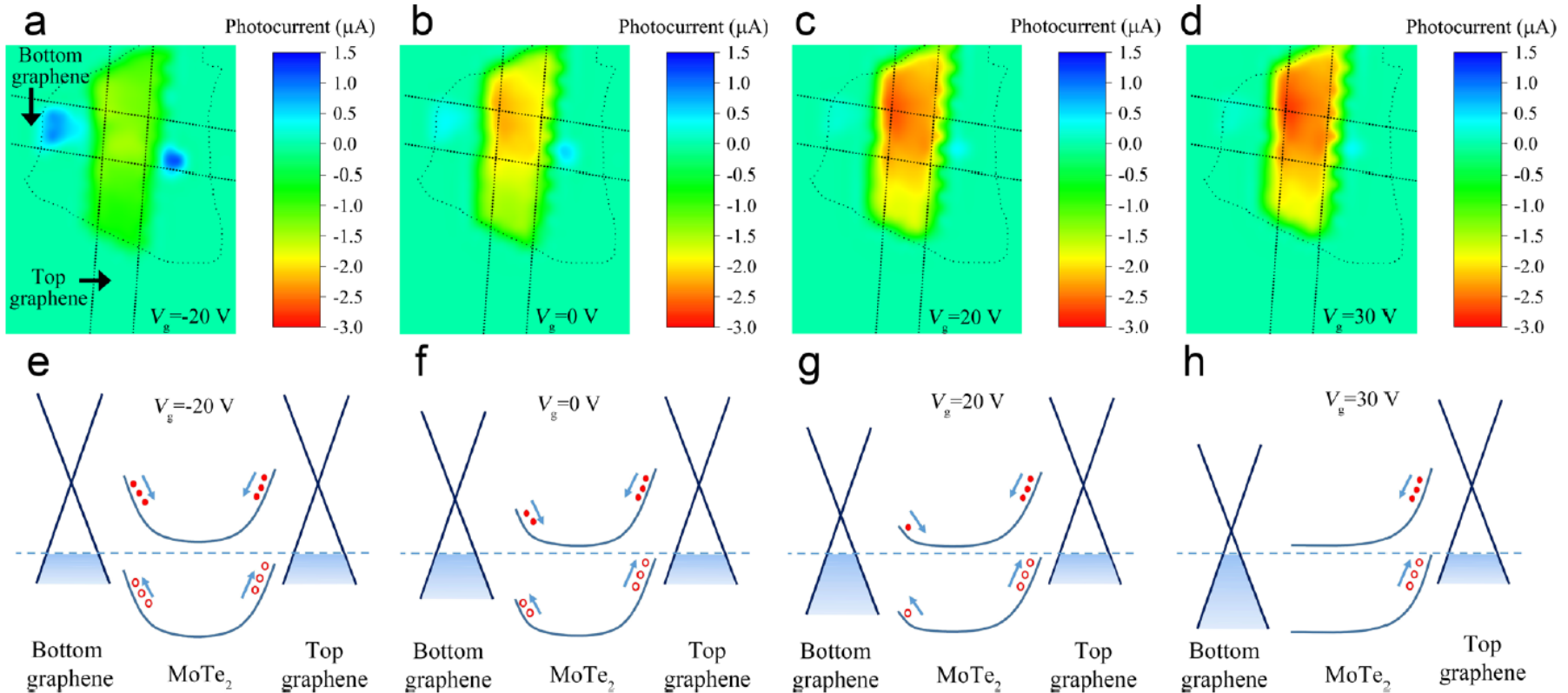
Detailed Electrical and Photoresponse Properties



- The I_{ds} - V_{ds} curves asymmetric transport behaviors.
- Back-to-back Schottky barriers with different Schottky barrier heights
- Ambient water vapor and oxygen p-doping of the top graphene
- The I_{sc} and V_{oc} increase with the back-gate

Photocurrent Generation

At $V_g=0$, the Schottky barrier height at G_T/MoTe_2 is higher than that at G_B/MoTe_2

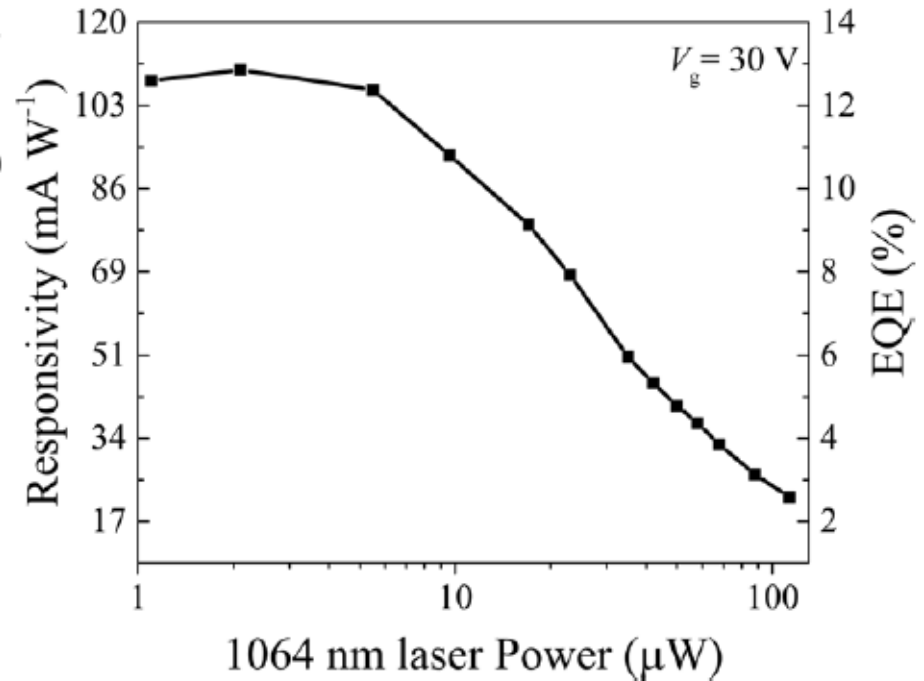
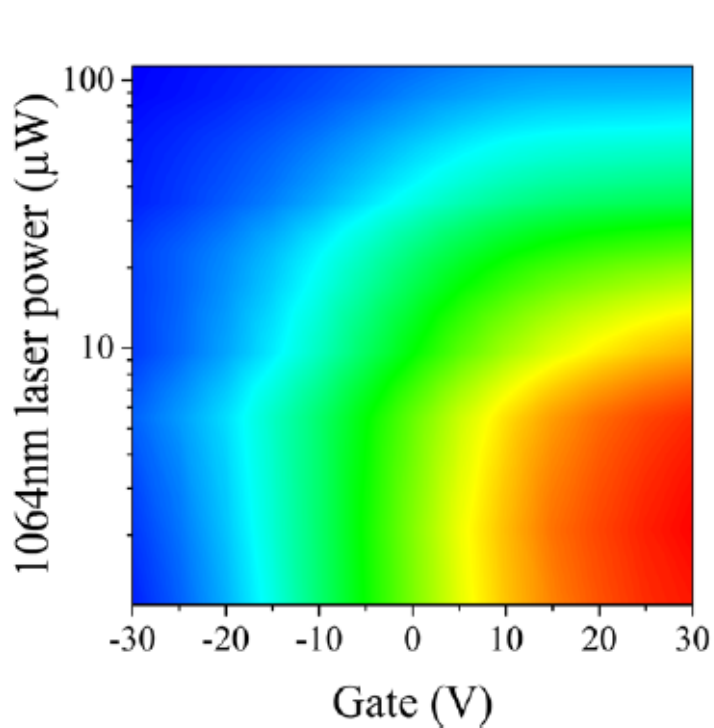


Due to the screening effect from the bottom graphene and MoTe_2 , the Schottky barrier height at G_T/MoTe_2 is less sensitive to the back gate.

Photocurrent @ G_B/MoTe_2 ↓

Photocurrent @ G_T/MoTe_2 ↑

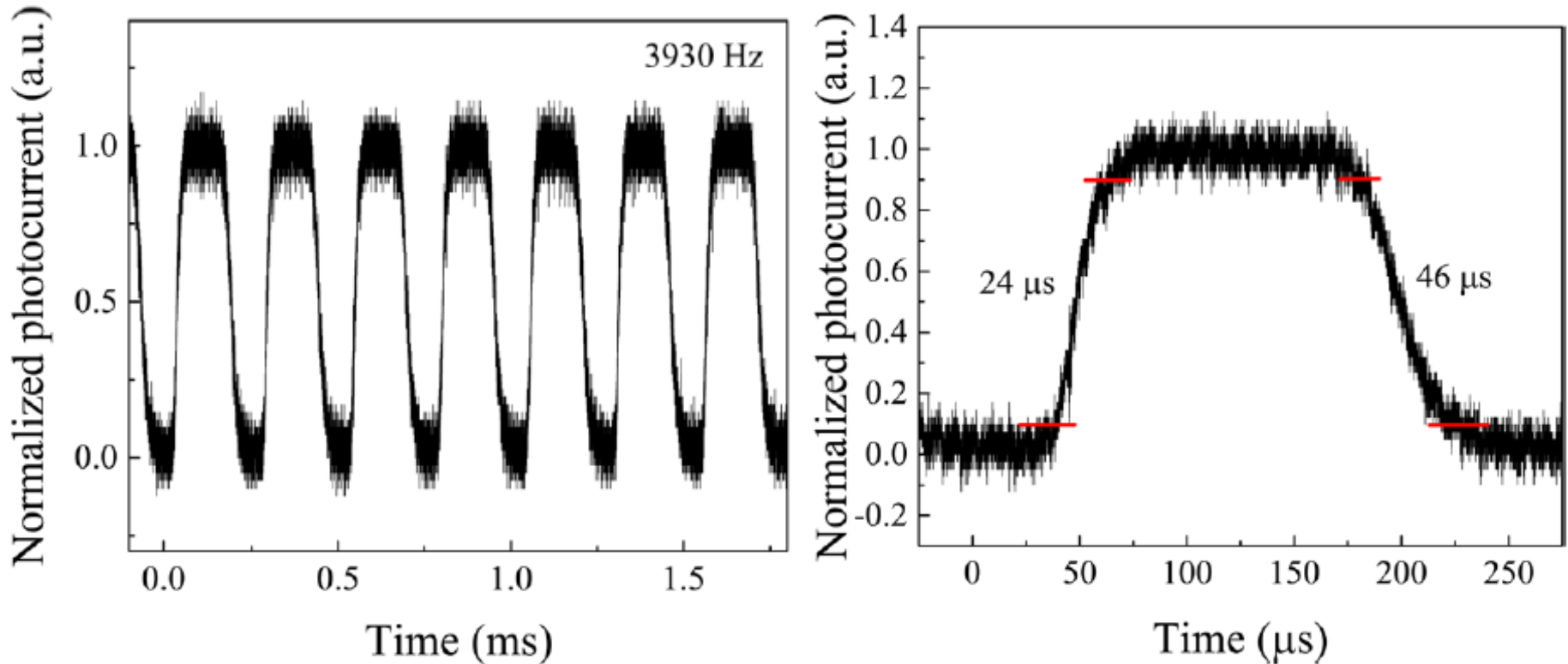
NIR Photoresponse Performance



- Back-gate voltage
- Laser power

- When the power $< 5 \mu\text{W}$
- Responsivity $\sim 110 \text{ mA W}^{-1}$
 - EQE $\sim 12.6\%$

Temporal Photoresponse



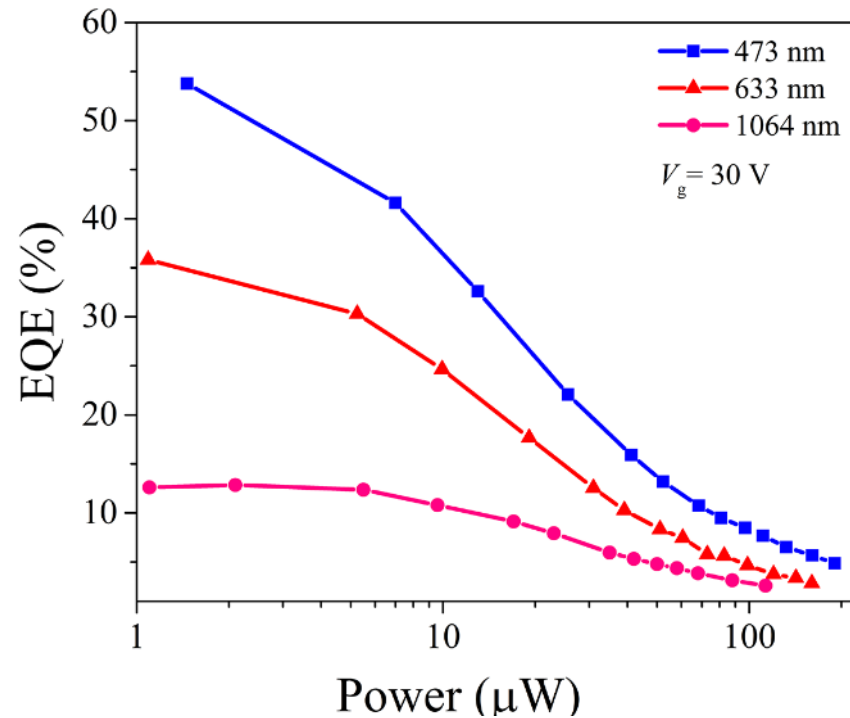
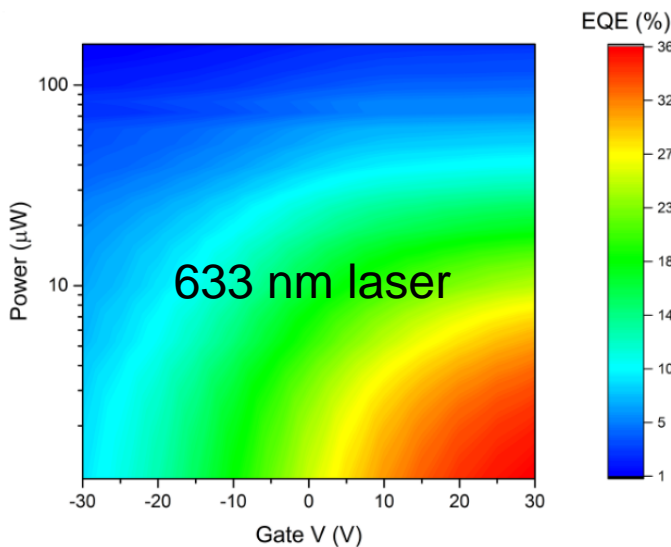
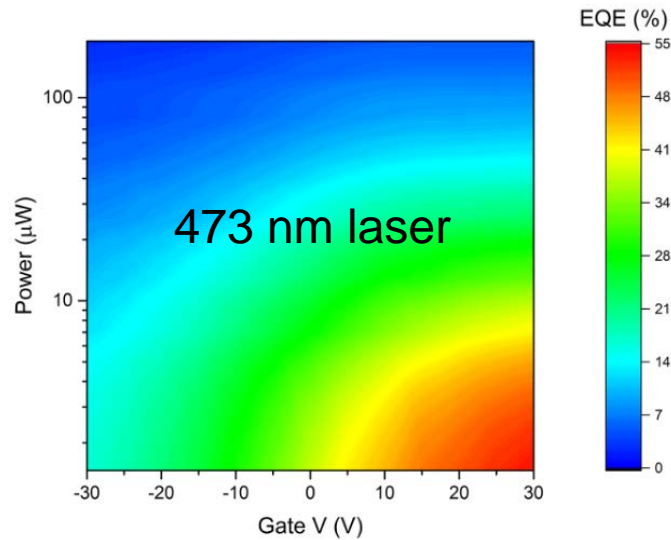
- Rise and fall times: **24 μs** , **46 μs**
- Considering the intrinsic response time of the mechanical chopping process ($\sim 10\mu\text{s}$), the rise and fall times are **even shorter**.

Comparison

Materials	V_{ds} (V)	Responsivity (mA W ⁻¹)	Response time (ms)	Wavelength
MoTe ₂	0	110	0.024	1064 nm
b-P	0.2	<5	1	400 - 997 nm
b-P/MoS ₂	3	153.4	0.015	1550
MoS ₂	0.8	5200	44500	1070 nm
MoS ₂	1	0.09	-	850 nm
MoS ₂ /Si	0	300	0.003	808
Bi/WS ₂ /Si	0	420	<100	635
MoS ₂	0	68	-	633 nm
MoS ₂	0	220	<0.05	488 nm
WS ₂	0	>100	-	488 nm
SnS ₂	2	8.8	0.005	457 nm
InSe	10	1.57×10 ⁵	40-50	633
InSe	1	4×10 ⁷	1	633
InSe	50	486	0.06	543

An overall high performance

Photoresponse Properties in Visible Range

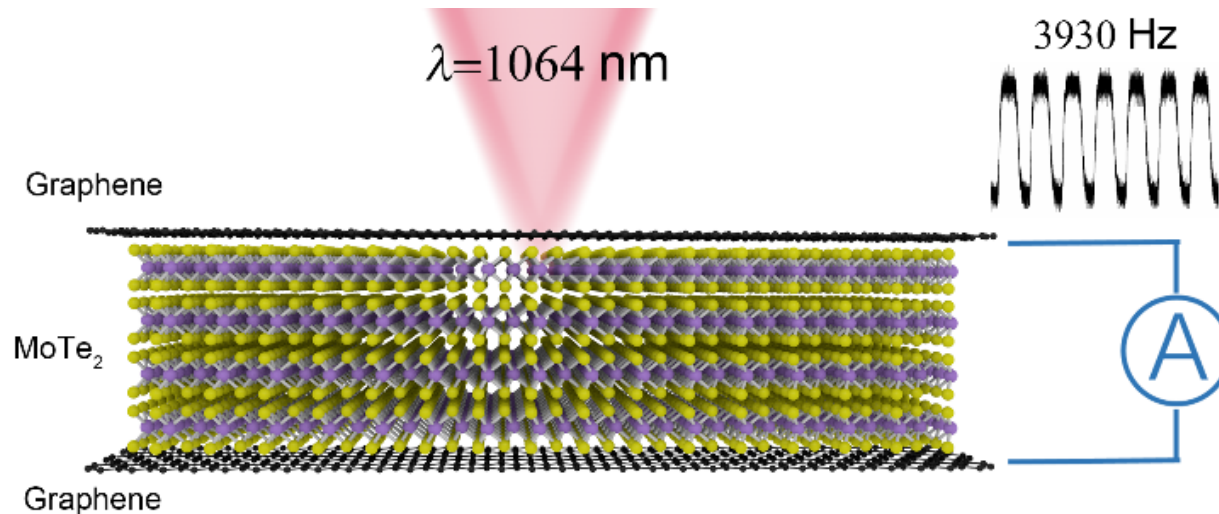


@ 473 nm, $R \sim 205 \text{ mA W}^{-1}$ (EQE $\sim 53.8\%$)

@ 633 nm, $R \sim 183 \text{ mA W}^{-1}$ (EQE $\sim 35.8\%$)

Conclusion

- Graphene-MoTe₂-Graphene vertical vdWs heterostructure, which has uniformly large photoresponse area and short transmit distance between the source and drain
- Self powered with high responsivity(110 mA W⁻¹), high speed (24 μs) in the NIR range
- Photo response can be tuned by the back-gate voltage



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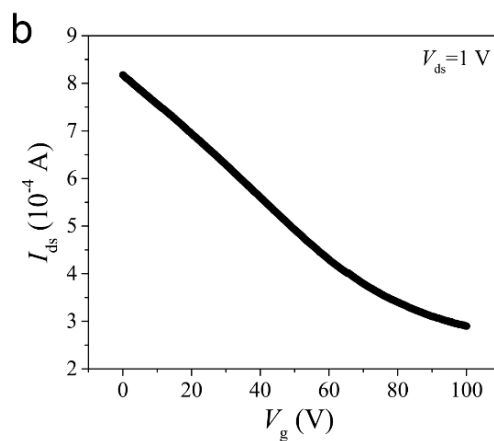
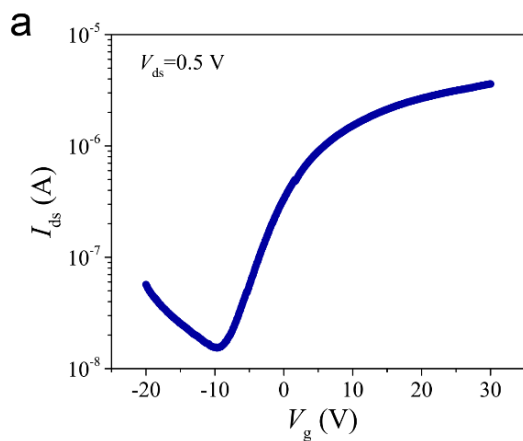
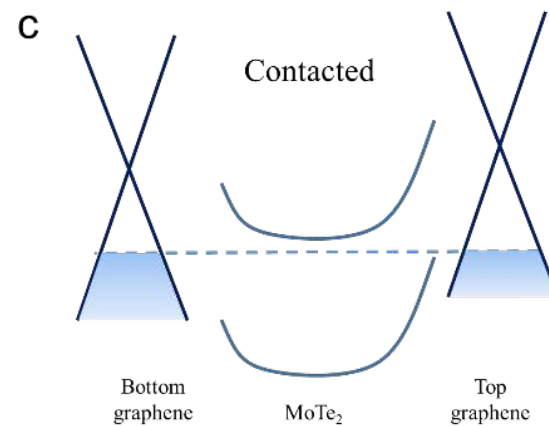
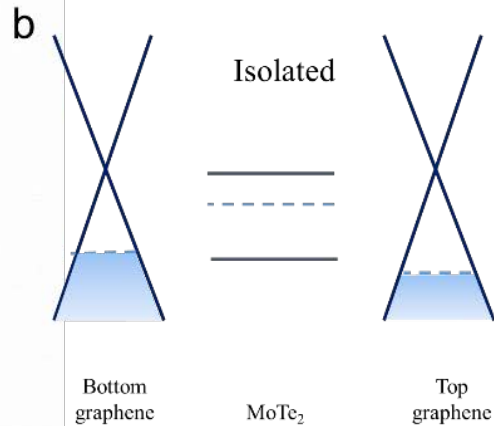
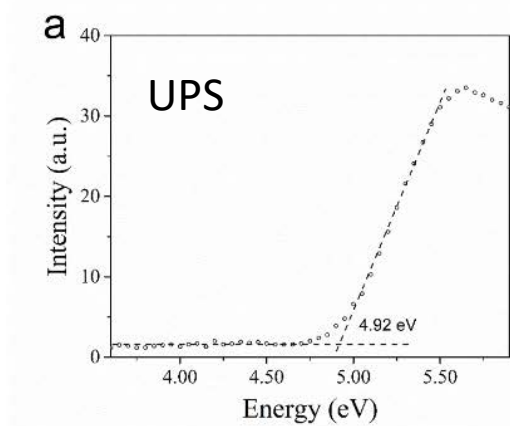
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Thank you!



The work function of MoTe₂ was reported to be 4.1~4.3 eV.

